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PATENT
81877.0001
Waller

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Norikazu MIZUNO, et al.

Serial No: 09/670,917

Filed: September 29, 2000

For: SEMICONDUCTOR DEVICE
MANUFACTURING METHOD AND
APPARATUS FOR REMOVING SILICON
NITRIDE FORMED IN A REACTION
CONTAINER (AS AMENDED)

AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Art Unit: 2822

Examiner: GUERRERO, M.

I hereby certify that this correspondence
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Commissioner for Patents
Washington D.C. 20231, on

June 20, 2002

Date of Deposit

Kimberly Yee 06/20/02

Name Date

Kimberly Yee
Signature

Dear Sir:

This is in response to the Office Action dated December 20, 2001. Enclosed are a petition for a three-month extension of time and a check for the requisite fee, so that the period for response runs to and includes June 20, 2002. Please amend the above-referenced application as follows:

IN THE TITLE:

Please replace the title of the invention with the following text:

"SEMICONDUCTOR DEVICE MANUFACTURING METHOD AND
APPARATUS FOR REMOVING SILICON NITRIDE FORMED IN A REACTION
CONTAINER"